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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/044,427	11/09/2001	Thomas Herman	IR-1641	1934
7590 07/18/2003 OSTROLENK, FABER, GERB & SOFFEN, LLP		EXAMINER		
	E OF THE AMERICAS NY 10036-8403		LEWIS, MONICA	
			ART UNIT	PAPER NUMBER
			2022	

DATE MAILED: 07/18/2003

Please find below and/or attached an Office communication concerning this application or proceeding.

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	Application No.	Applicant(s)	200		
Advisory Action	10/044,427	HERMAN ET AL.			
Advisory Action	Examiner	Art Unit			
	Monica Lewis	2822			
The MAILING DATE of this communication appe	ears on the cov r sheet with the c	correspondence add	ress		
THE REPLY FILED 24 June 2003 FAILS TO PLACE THE Therefore, further action by the applicant is required to a final rejection under 37 CFR 1.113 may only be either: (condition for allowance; (2) a timely filed Notice of Appe Examination (RCE) in compliance with 37 CFR 1.114.	avoid abandonment of this application appl	cation. A proper re ch places the appli	ply to a cation in		
PERIOD FOR RE	EPLY [check either a) or b)]				
a) The period for reply expires <u>3</u> months from the mailing date of					
b) The period for reply expires on: (1) the mailing date of this Advevent, however, will the statutory period for reply expire later the ONLY CHECK THIS BOX WHEN THE FIRST REPLY WAS 706.07(f). Extensions of time may be obtained under 37 CFR 1.136(a). The data.	nan SIX MONTHS from the mailing date o FILED WITHIN TWO MONTHS OF TH	f the final rejection. E FINAL REJECTION. \$	See MPEP		
nave been filed is the date for purposes of determining the period of exten B7 CFR 1.17(a) is calculated from: (1) the expiration date of the shortened b) above, if checked. Any reply received by the Office later than three moverned patent term adjustment. See 37 CFR 1.704(b).	sion and the corresponding amount of the distatutory period for reply originally set in	e fee. The appropriate ex the final Office action; or	tension fee under (2) as set forth in		
1. A Notice of Appeal was filed on Appellant' 37 CFR 1.192(a), or any extension thereof (37 CF					
2. The proposed amendment(s) will not be entered b	ecause:				
(a) they raise new issues that would require furth	er consideration and/or search (	(see NOTE below);			
(b) ☐ they raise the issue of new matter (see Note below);					
(c) ☐ they are not deemed to place the application issues for appeal; and/or	in better form for appeal by mat	terially reducing or	simplifying the		
(d) they present additional claims without cance	ling a corresponding number of	finally rejected clair	ms.		
NOTE:					
3. Applicant's reply has overcome the following rejection.					
<ol> <li>Newly proposed or amended claim(s) would canceling the non-allowable claim(s).</li> </ol>	d be allowable if submitted in a s	separate, timely file	d amendment		
5. ☐ The a) ☐ affidavit, b) ☐ exhibit, or c) ☐ request for application in condition for allowance because: Se		sidered but does No	OT place the		
6. The affidavit or exhibit will NOT be considered be raised by the Examiner in the final rejection.	cause it is not directed SOLELY	to issues which we	ere newly		
7. For purposes of Appeal, the proposed amendmen explanation of how the new or amended claims w			and an		
The status of the claim(s) is (or will be) as follows.	:				
Claim(s) allowed:					
Claim(s) objected to:					
Claim(s) rejected:					
Claim(s) withdrawn from consideration:					
8. The proposed drawing correction filed on is	s a)□ approved or b)□ disap	proved by the Exar	niner.		
9.  Note the attached Information Disclosure Stateme	ent(s)( PTO-1449) Paper No(s).	4			
10. ☐ Other:	SUPE TE	AMIR ZARABIAN RVISORY PATENT EX CHNOLOGY CENTER	aminer 2800		

Continuation of 5. does NOT place the application in condition for allowance because: Applicant argues that "there is no disclosure in Huang or any other cited refer nce, which teaches or suggests making the source regions in a planar device of such dimensions in orde to improve the ability of the device to withstand punch through." However, Huang discloses a source region that is less than .3 microns (For Example: See Column 6 Lines 24-64).